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PATENT
34261-8500

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ge et al.

Serial No.: 10/680,960

Filed: October 7, 2003

For: PHOTORESIST COATING PROCESS FOR
MICROLITHOGRAPHY

Examiner: Unknown

Group Art Unit: Unknown

Conf. No.: 6075

Date: July 13, 2005

Irvine, California 92614

SUPPLEMENTAL
INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In an attempt to fully comply with the duty of disclosure set forth in 37 C.F.R. § 1.56 and in conformance with 37 C.F.R. §§ 1.97 and 1.98, applicant wishes to bring to the attention of the U.S. Patent Office the following references:

U.S. Patent No. 5,762,708
U.S. Patent No. 6,174,561
European Patent EP 617,332
Anonymous Abstract entitled "Process to Clean Metal Surfaces Prior to Photoresist Apply"
(XP 007116262A) dated April 1991

Form PTO-A820 is attached.

The undersigned attorney hereby certifies that each item contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart international application not more than three months prior to filing this statement.

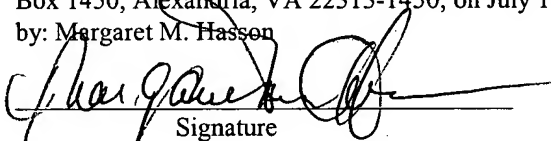
The written opinion of the International Searching Authority, the European Patent Office, for the counterpart PCT application PCT/US2004/023587 is also submitted herewith.

If the Examiner believes that a telephone conference would help further the prosecution of this case, he is respectfully requested to contact the undersigned attorney at the listed telephone number.

Applicants believe there is no fee due with this submission, however, if it is deemed a fee is due, the Director is hereby authorized to charge or credit Deposit Account 19-2814 as appropriate for this submission.

If there are any questions with regards to the submission, the undersigned attorney can be contacted at the listed phone number.

I hereby certify that this correspondence is being deposited with the U.S. Postal Service as first class mail in an envelope addressed to: Commissioner for Patent, PO Box 1450, Alexandria, VA 22313-1450, on July 13, 2005 by: Margaret M. Hasson



Signature

Date of Signature: July 13, 2005

Very truly yours,

SNELL & WILMER LLP



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949/253-2720

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional)		Application Number	
				34261-8500		10/380,960	
				Applicant(s)			
				Ge et al.			
				Filing Date		Group Art Unit	
				10/07/2003		1756	

U. S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		5,762,708	06/09/1998	Motada et al.	118	52	
		6,174,561	01/16/2001	Taylor	427	96	

U.S. PATENT APPLICATION PUBLICATIONS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
		617,332	09/28/1994	EP				

OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>	
	Anonymous, "Process to Clean Metal Surfaces Prior to Photoresist Apply" (XP 007116262A) Research Disclosure – Kenneth Mason Publications, Vol. 324, No. 31, Abstract, April 1991
	Written Opinion of the International Searching Authority, the European Patent Office for the PCT counterpart application PCT/US2004/023587

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.